

Chroma

Create Your Own Testing Innovation.

2014

Chroma 7935

晶粒外觀檢查機

Test
turnkey **and** **Automation**
Solution
provider

2014年2月11日

- 產品規格介紹
 - 7935
 - 7936
- 適用產品範圍
- 重點功能說明
- 檢查項目
- 報表及分析工具
- 結論

CMOS Image Sensor Inspection Items 影像感測器檢查項目



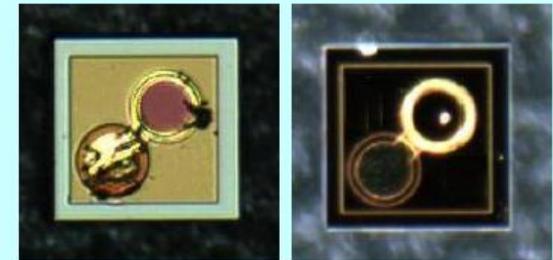
- Ball Missing 錫球缺少
- Ball Chipping 錫球崩缺
- Ball Shift 錫球位移
- Lead Short 引線短路
- Lead Open 引線斷路
- Lead Notch 引線缺角

LED Inspection Items 發光二極體檢查項目



- Pad Defect 電極缺陷
- Pad Residue 電極殘留
- ITO Peeling 發光區剝落
- Finger Broken 斷線
- Mesa Abnormality 切割道異常
- Epi Defect 磊晶缺陷
- Chipping 崩缺
- Chip Residue 晶粒殘留

Laser Diode Inspection Items 雷射二極體檢查項目



- Photosensitive Region Defect 光窗缺陷
- Bond Pad Defect 鐳墊區缺陷
- Passivation Film Defect 外膜缺陷
- Scribe Line Defect 切割道缺陷
- Chipping 晶粒崩缺
- Double Chip 雙晶

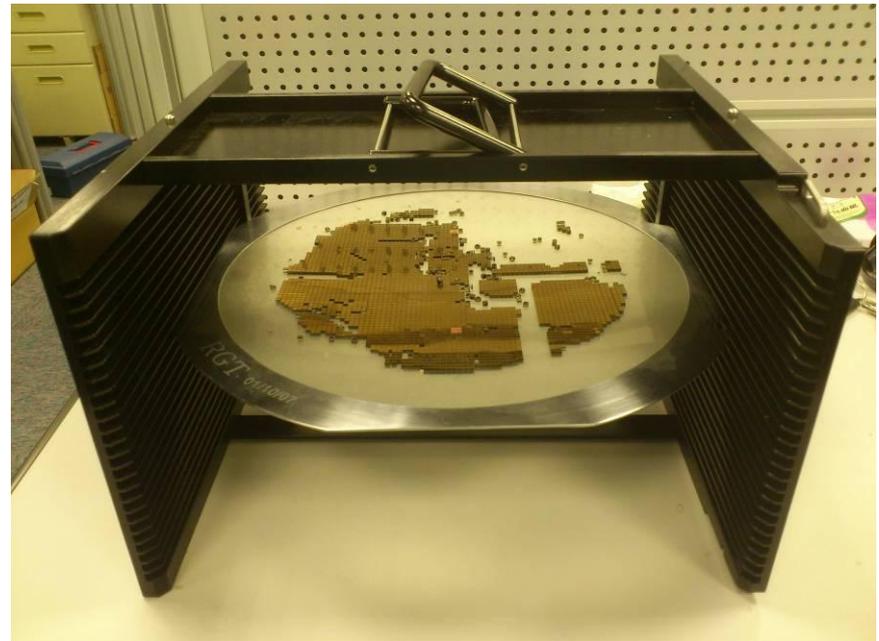
- 適用晶圓尺寸
 - 2"~6" (擴張後尺寸小於8吋)
- 適用晶粒尺寸
 - 6mil~100mil (2X lens)
- 7935可程式控制更換2X, 5X物鏡
 - 2X物鏡系統解析度為 $1.72\mu\text{m}/\text{pixel}$
 - 5X物鏡系統解析度為 $0.7\mu\text{m}/\text{pixel}$
- 具備多種光源可依不同缺陷調配
 - 同軸光、環型光、背光
- 自動化卡匣上下片
 - 視機型配置1~2個卡匣，每個卡匣可裝12片晶圓
- 檢測時間
 - 2"矽片使用2X物鏡可在2分鐘內檢測完成*



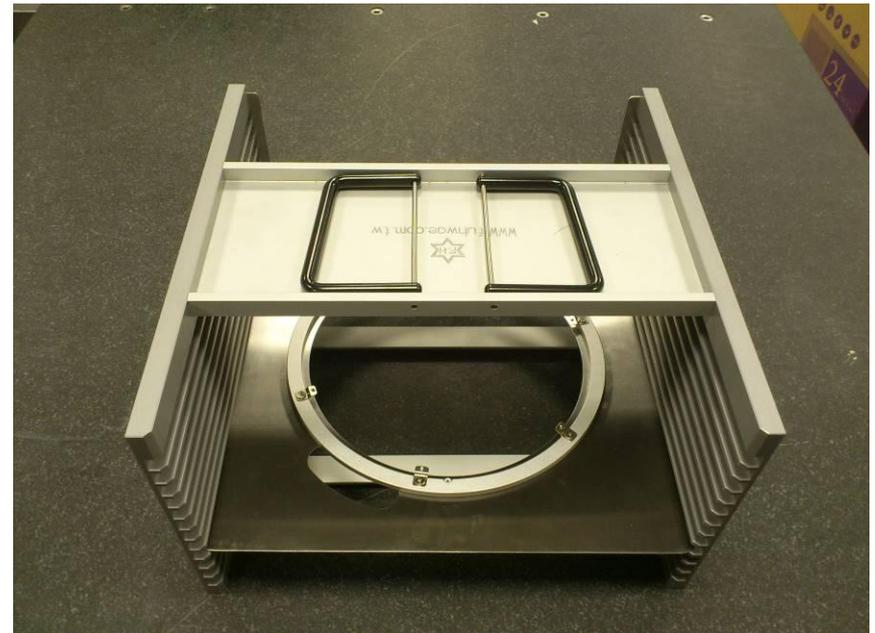
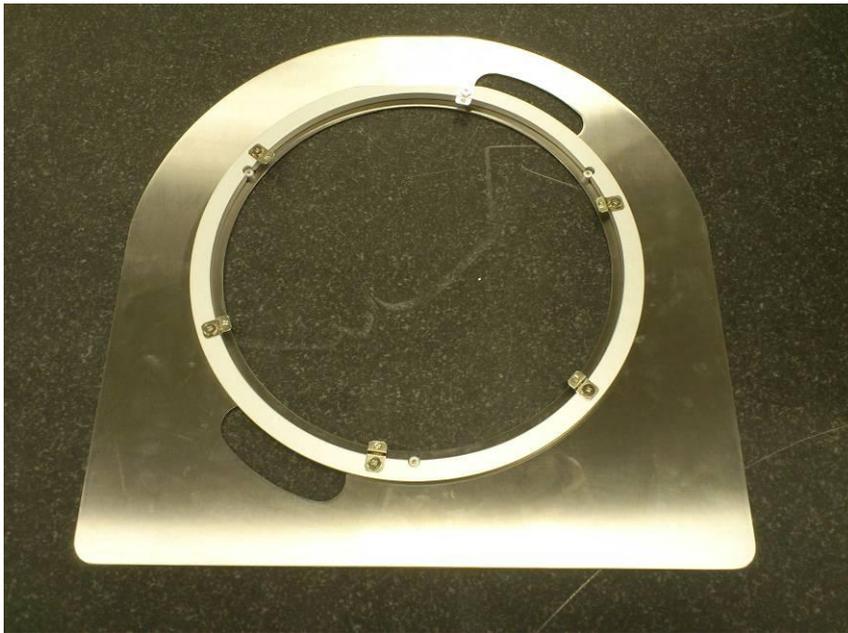
*測試條件為使用兩種光源以及晶粒尺寸為20mil

適用卡匣

1. Wafer Frame (K&S DISCO type)



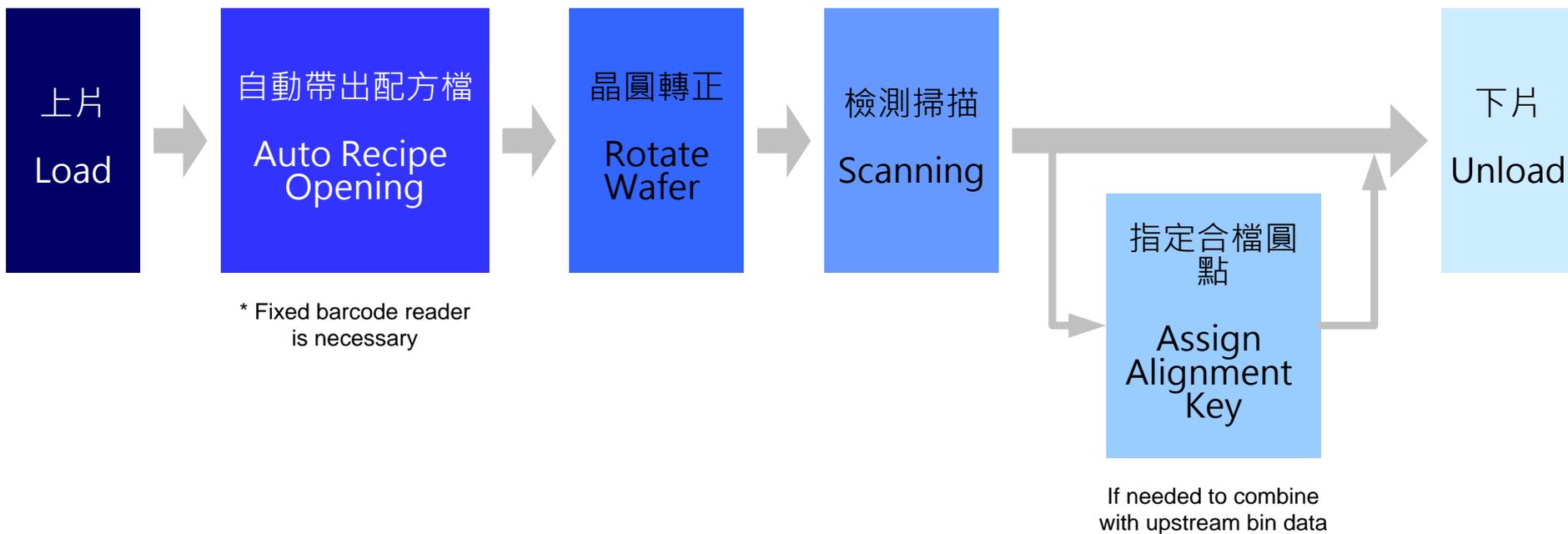
2. Expander Ring (Grip Ring) + Ring Holder



* 專利申請中

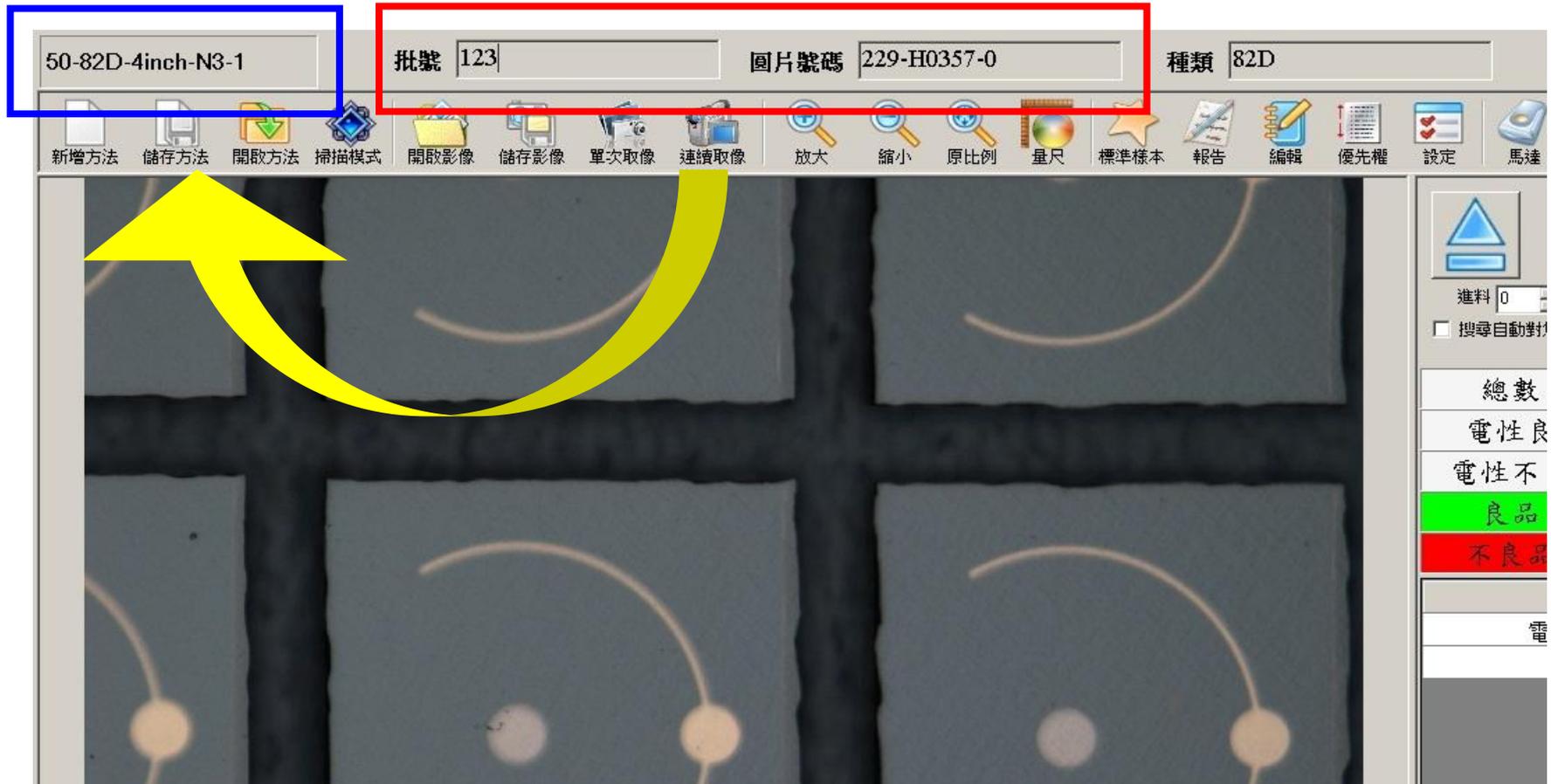
軟體功能介紹

全自動化流程

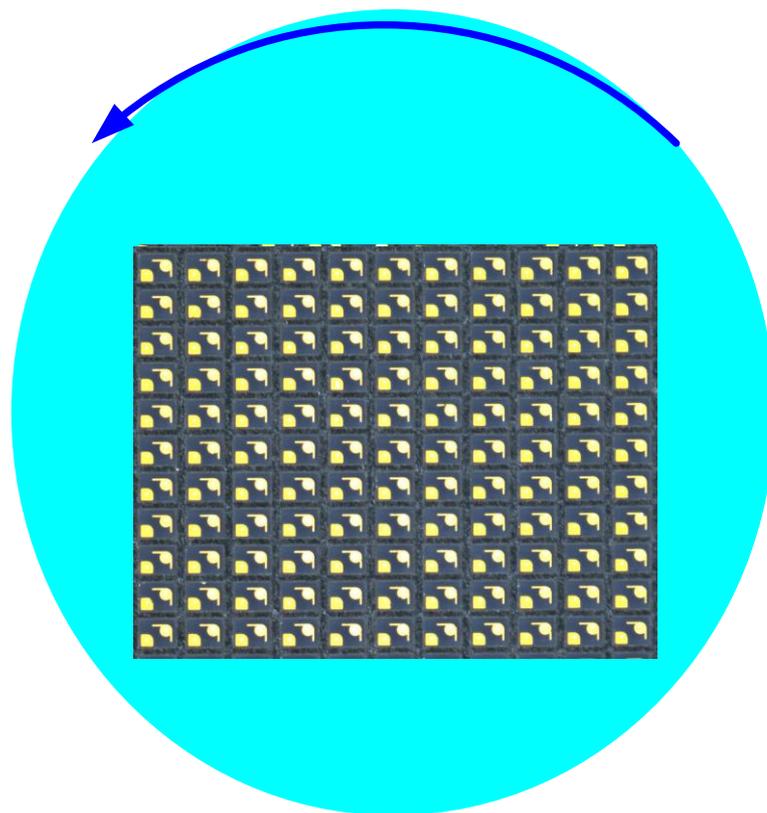


設定完成後，不再需要人員逐片操作

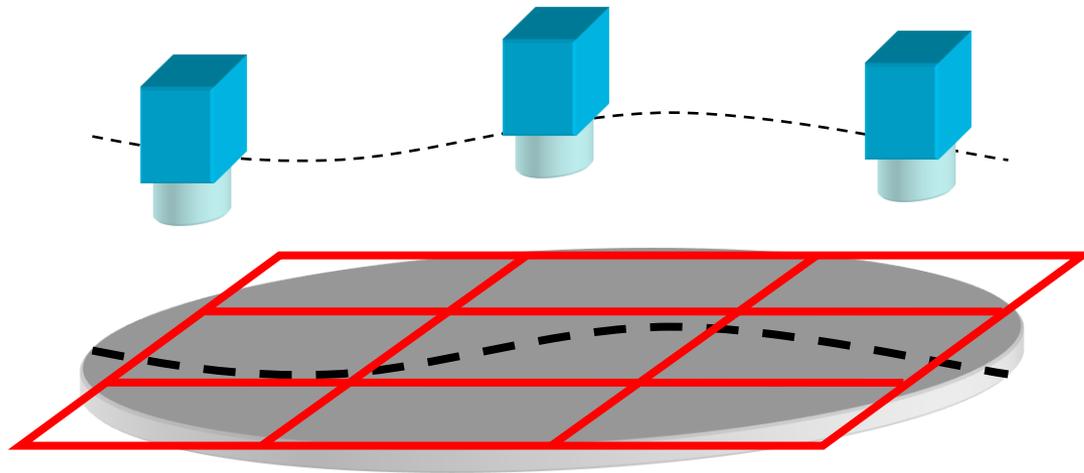
- 可依Wafer ID或Lot No之關鍵字帶出配方檔



- 上片後自動依晶粒水平排列狀況進行轉正



- 軟體自動對焦可以克服因藍膜或晶粒造成的表面不平現象
- 可設定自動對焦的頻率(次數)

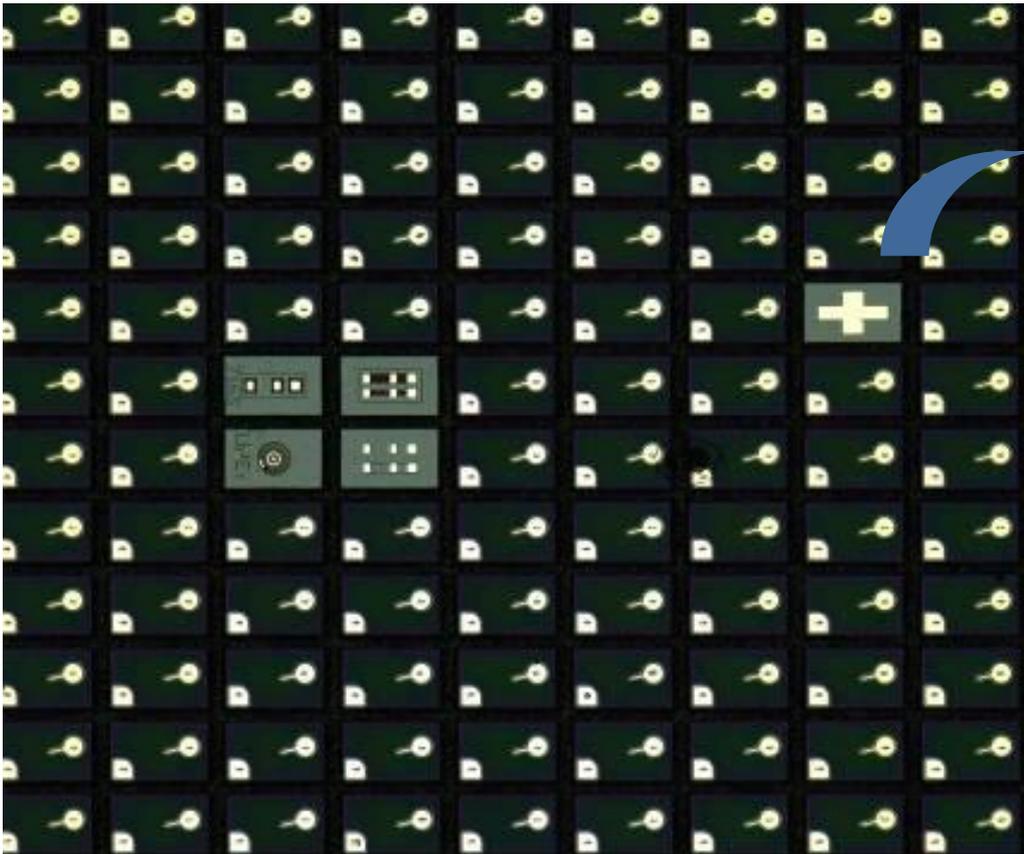


- 掃描時可判斷晶粒邊緣，自動規劃掃描路徑



自動化指定合檔原點(1)

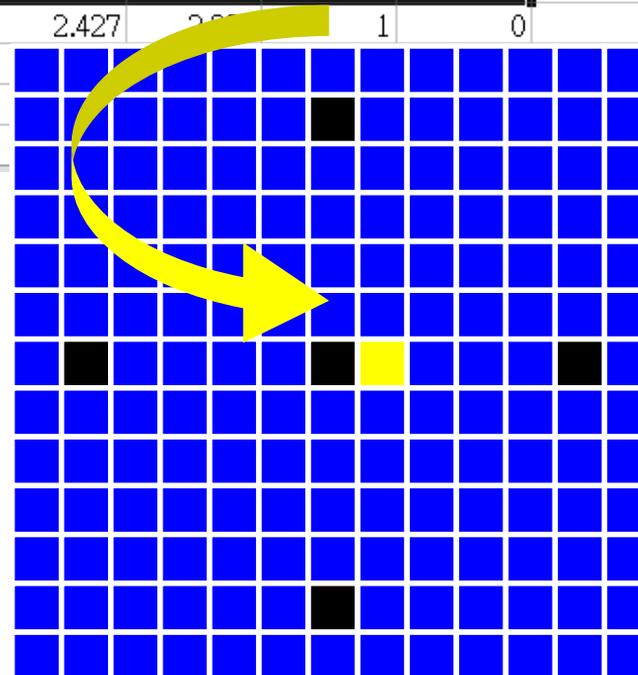
- 適用於圓片模式
- 設定定位圖案以作為合檔原點



自動化指定合檔原點(2)

- 適用於破片模式
- 可由上游分類檔尋找“非晶粒”座標，並與AOI檢測座標比較，自動找出合檔原點

60	TEST	BIN	POLAR	VF1	VF2	VF3	VF4	PosX	PosY
11149	11089	999	1	3.224		2.439	2.226	-3	0
11150	11090	999	1	3.225		2.439	2.234	-2	0
11151	11091	999	1	3.228		2.441	2.223	0	0
11152	11092	999	1	3.229		2.427	2.223	1	0
11153	11093	999	1	3.233					
11154	11094	999	1	3.233					
11155	11095	999	1	3.235					



- Normal Chip
- Removed Chip
- As Original Point

- 可用於分析配方檔、調整配方檔及良率變化預估，並且不影響機台產能

Edit Parameters and Criteria

項目	標準	比較	輸入值
<input type="checkbox"/> 電極線個數	1.00	大於	3.00
<input checked="" type="checkbox"/> 電極線交集電極...	6.00	小於	100.00
<input checked="" type="checkbox"/> 電極線斷個數	1.00	大於	0.00
<input type="checkbox"/> 電極線長度比例	1.00	小於	100.00
<input checked="" type="checkbox"/> 垂直與水平電極...	7.00	小於	100.00

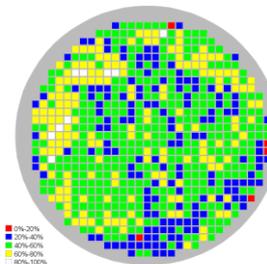
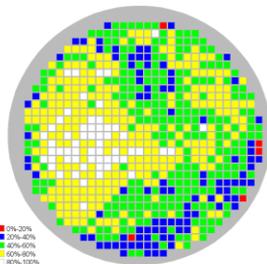
Inline Scan



Image Data



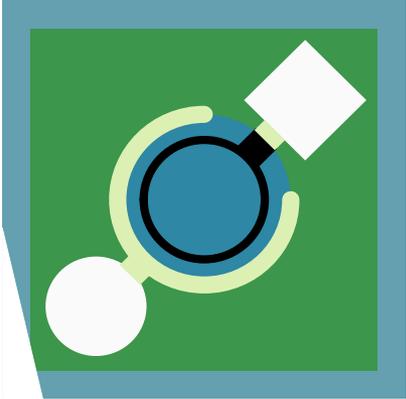
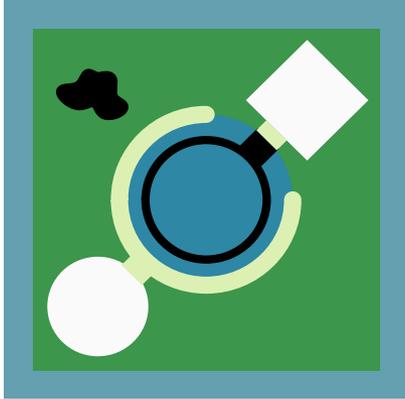
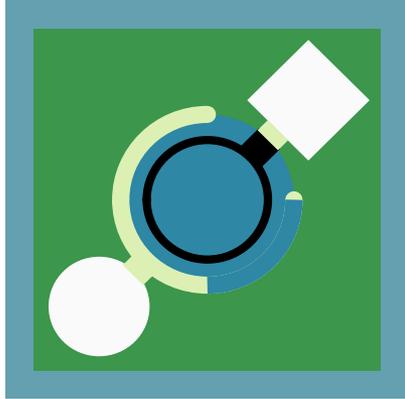
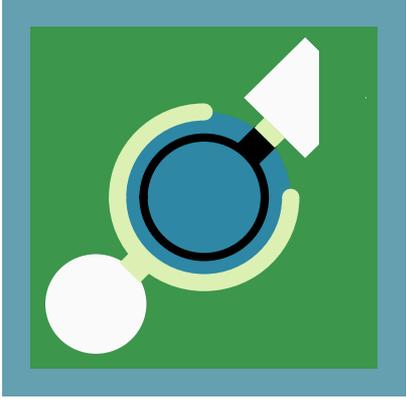
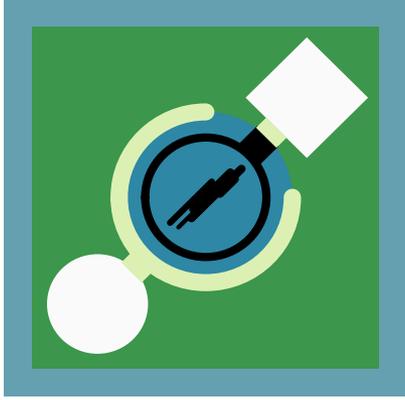
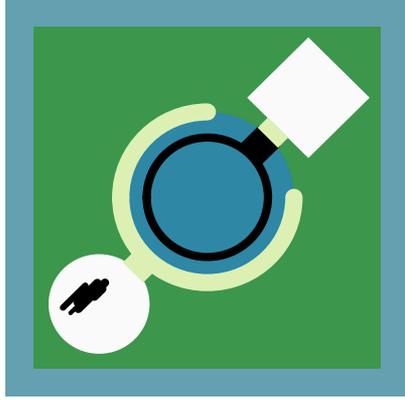
Offline Scan

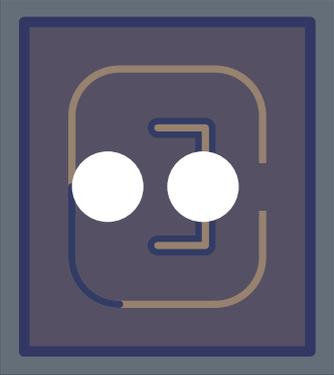
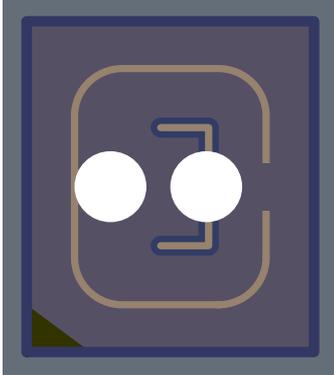
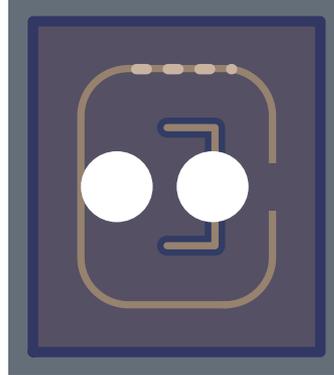
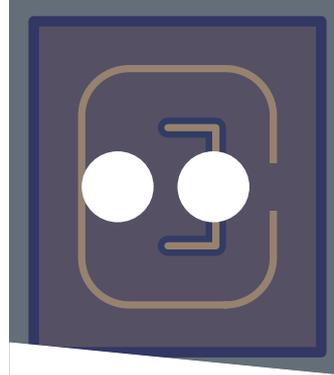
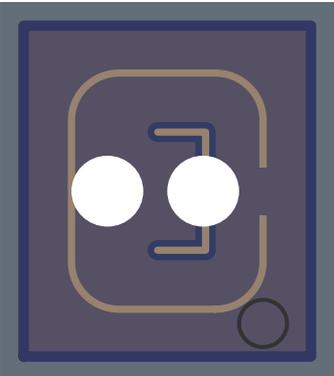
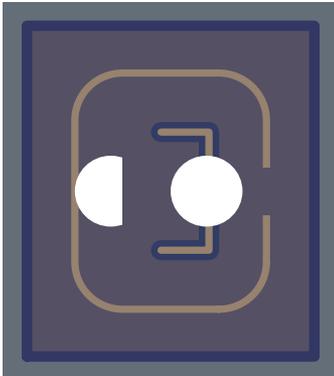
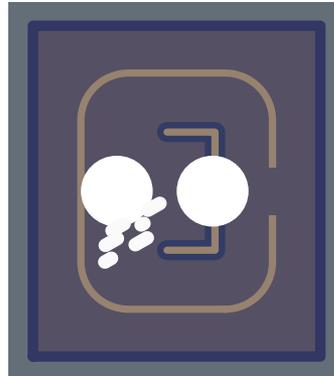
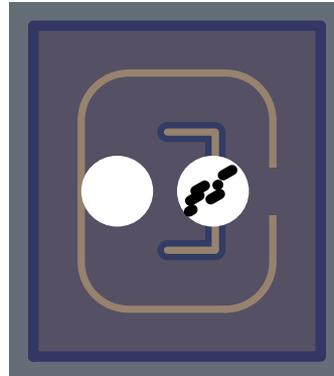


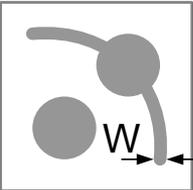
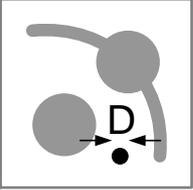
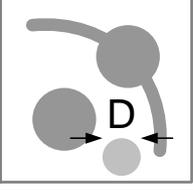
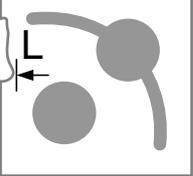
檢查項目

- 提供Layout繪製工具，可針對不同產業的晶片繪製檢測範圍
- 標準樣本編輯時間一般可在20分鐘內完成



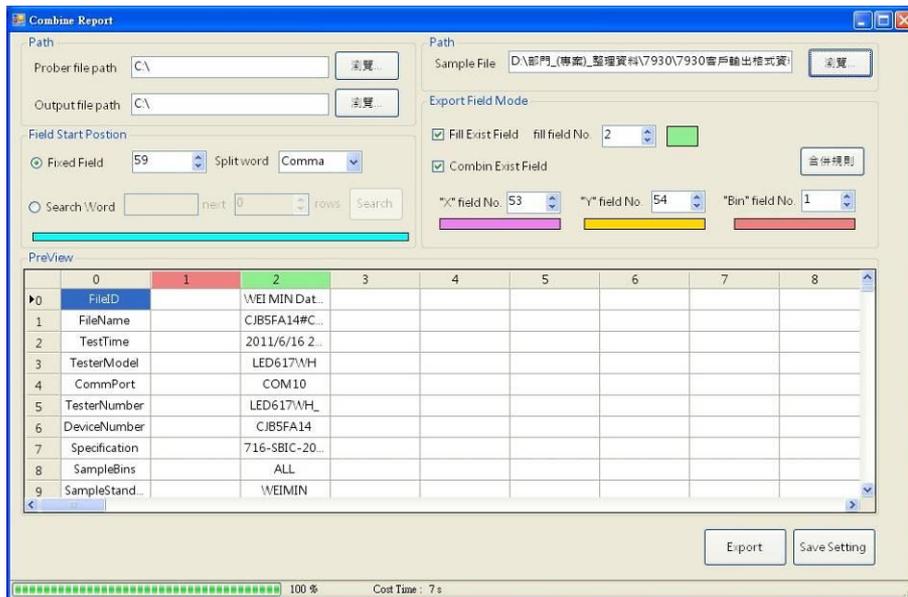
<p>Chipping 晶粒崩缺</p>	<p>Blemish 汙染</p>	<p>Branch Broken 電極線斷</p>
 <p>A schematic diagram of a photo diode on a green substrate. It features a central blue circle, a white circle to the left, and a white diamond to the top right. A yellow ring surrounds the central blue circle. A black line connects the central blue circle to the white diamond. A white chip is missing from the top right corner of the yellow ring.</p>	 <p>A schematic diagram of a photo diode on a green substrate, identical to the first diagram. A black irregular stain is present in the upper left area of the green substrate.</p>	 <p>A schematic diagram of a photo diode on a green substrate, identical to the first diagram. A black line representing an electrode is broken at the top right corner.</p>
<p>Pad Damage 電極缺少</p>	<p>Scratch 光窗刮傷</p>	<p>Pad Scratch 電極刮傷</p>
 <p>A schematic diagram of a photo diode on a green substrate, identical to the first diagram. A white triangular electrode pad is missing from the top right corner.</p>	 <p>A schematic diagram of a photo diode on a green substrate, identical to the first diagram. A black diagonal scratch is present on the central blue circle.</p>	 <p>A schematic diagram of a photo diode on a green substrate, identical to the first diagram. A black diagonal scratch is present on the white circle at the bottom left.</p>

<p>Finger Broken 電極線斷</p>	<p>Peeling 發光區剝落</p>	<p>Finger Scratch 電極刮傷</p>	<p>Chipping 晶粒崩缺</p>
			
<p>Epitaxy Defect 磊晶缺陷</p>	<p>Pad Lack 電極缺少</p>	<p>Pad Residue 電極殘留</p>	<p>Pad Scratch 電極刮傷</p>
			

Defect ITEM		SPEC	
		2X Objective (1.7um/pixel)	5X Objective (0.7um/pixel)
Finger/ Branch Width		$W > 5\mu\text{m}$	$W > 2\mu\text{m}$
High Contrast Defect (Grey value > 80)		$D > 5\mu\text{m}$	$D > 2\mu\text{m}$
Low Contrast Defect ($80 > \text{Grey value} > 40$)		$D > 20\mu\text{m}$	$D > 10\mu\text{m}$
Chipping/ Abnormal Dicing		$L > 10\mu\text{m}$	$L > 4\mu\text{m}$

詳盡的報表及分析工具

- 可合併上一站檢測設備之分類檔案，並輸出至服務器或挑揀機



可自由編輯合檔規則，指定合檔欄位

- 可儲存檢測後每一顆晶粒瑕疵量化資料供後續統計製程分析

	A	B	O	P	S	W	AH	AL
1	IsPass	Name	LED Length X	LED Length Y	LED Area	Pad Area	ITO Area	Pad Scratch Ratio
2	O	LED01	351	347	121350	3316.00,3382.00	60509	0.99
3	O	LED02	351	347	121658	3364.00,3408.00	60343	1.01
10	O	LED09	351	349	121759	3343.00,3356.00	60536	1
11	X	LED10	350	347	121135	3808.00,3437.00	59898	1.16
12	O	LED11	352	347	120940	3323.00,3422.00	60275	0.99
13	O	LED12	350	347	120912	3348.00,3414.00	60378	1
14	O	LED13	350	346	121016	3397.00,3424.00	60207	1.02
15	O	LED14	350.4	348.09	121148	3336.00,3397.00	60431	1
16	O	LED15	351	347	121259	3295.00,3380.00	60434	0.99
17	O	LED16	349	346	120724	3271.00,3406.00	60424	0.98
18	O	LED17	351.04	347.87	121613	3343.00,3431.00	60327	1
19	O	LED18	351	347	121458	3348.00,3394.00	60183	1
20	O	LED19	352	348	121216	3321.00,3378.00	60369	0.99

- 可產生每一片晶圓良率與各項統計資料

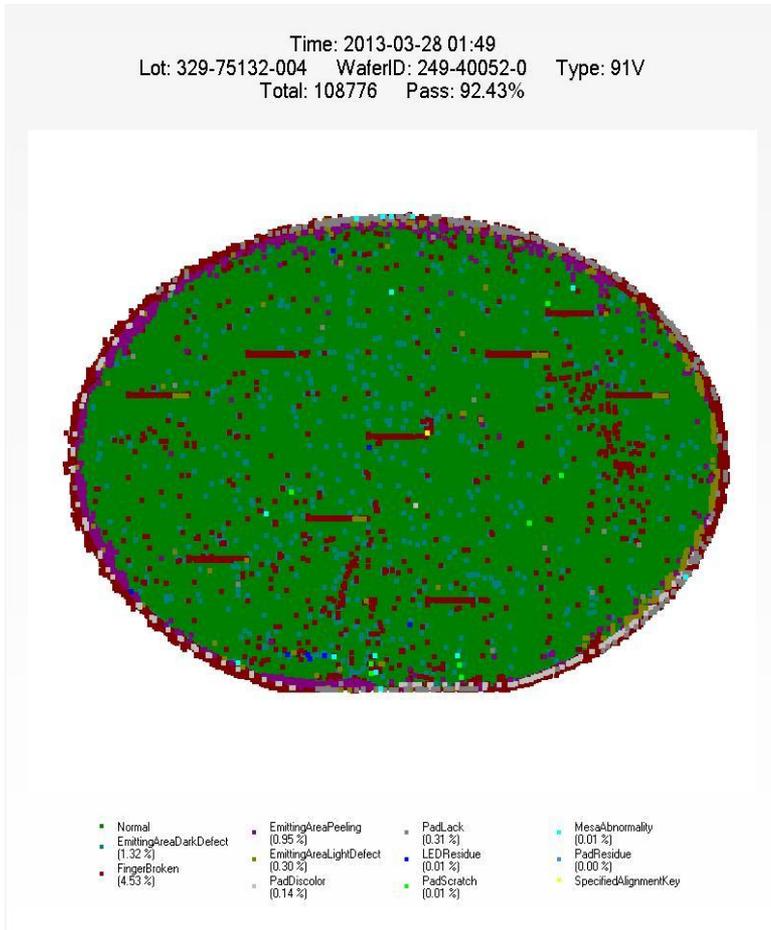
	A	B	C	D	E	F	G	H	I	J
	日期	晶片號碼	晶片	檢驗條件檔	總晶粒數	OK晶粒數	NG晶粒數	良率	切割良率	第一名瑕疵
1										
2	9/1/2011	AFB6XC03	919SB-I_1X	919SB-I	2037	2031	6	99.71%	100.00%	P電極污染
3	9/1/2011	AFB6NB13	919SB-I_1X	919SB-I	1972	1956	16	99.19%	99.95%	P電極污染
4	9/1/2011	AFB6WA26	919SB-I_1X	919SB-I	2731	2715	16	99.41%	99.93%	P電極污染
5										
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20										

提供良率、OK、NG顆數及瑕疵排名及數量供使用者自行編輯報表格式

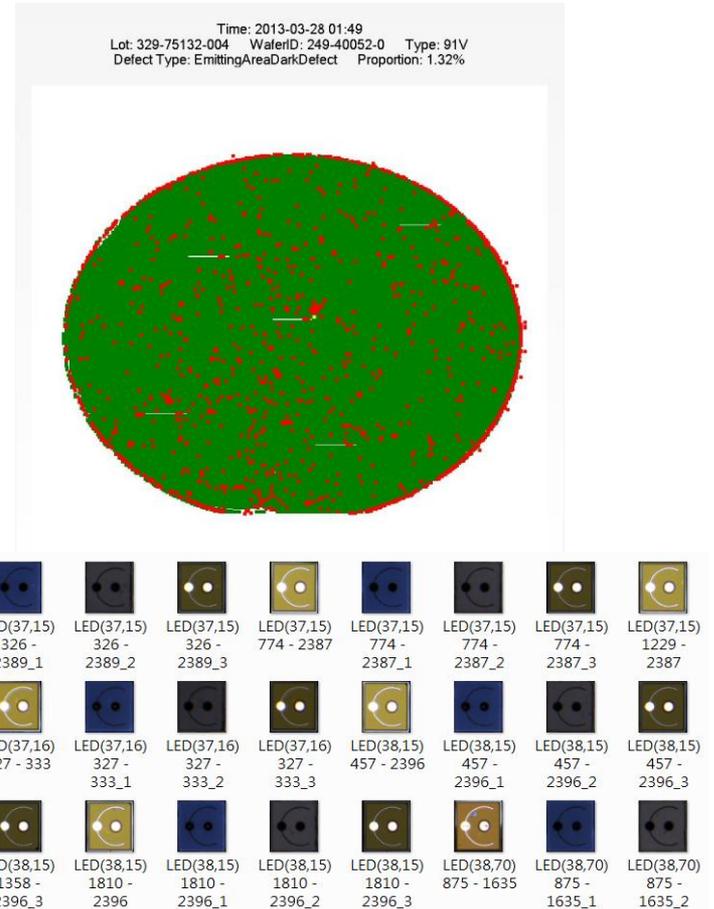
- 可選擇儲存原始影像，用於離線掃描
- 或是儲存瑕疵檢測結果影像，標示瑕疵區域



- 全部瑕疵分佈



- 單一瑕疵分佈及存圖



- 具備全自動化功能，減少人員操作錯誤問題
- 使用者可依自身需求選擇卡匣模組
- 模組化的演算法設計，可因應不同產業的檢測需求
- 與市面上Wafer AOI產品相比，具備更好之產能/價格比



Thank you very much